



Logic-compatible Gain Cell eDRAM

A Real Alternative to SRAM

Andrea Bonetti¹, Robert Gitterman², Adam

Teman², Alex Fish²,

Pascal Meinerzhagen¹, **Andreas Burg**¹

¹Telecommunications Circuits Laboratory, EPFL

²Bar-Ilan University



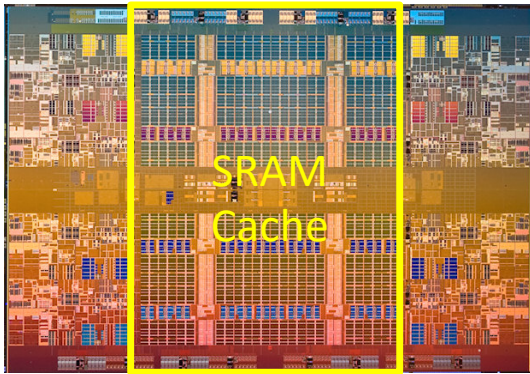
ÉCOLE POLYTECHNIQUE
FÉDÉRALE DE LAUSANNE

Memories Are the Limiting Factor for Cost and Energy Efficiency

- On-chip memories have a poor area density and often dominate chip area and cost in many computing systems
- Memory often accounts for >50% of the active power and for 100% of the power during sleep/standby periods in low-power systems

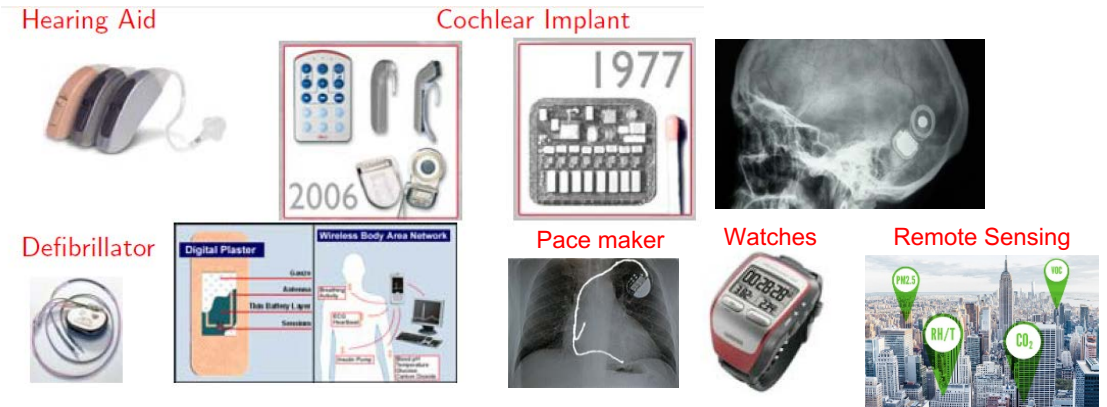
High-Performance Computing in PCs
and Data Centers

(Intel 8 core Xeon X7560)



Thousands of cores in a data center consume
mega Watts of power

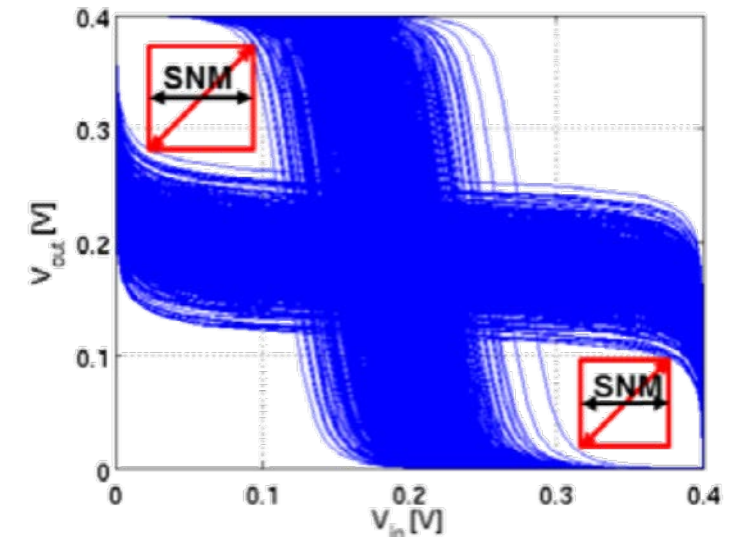
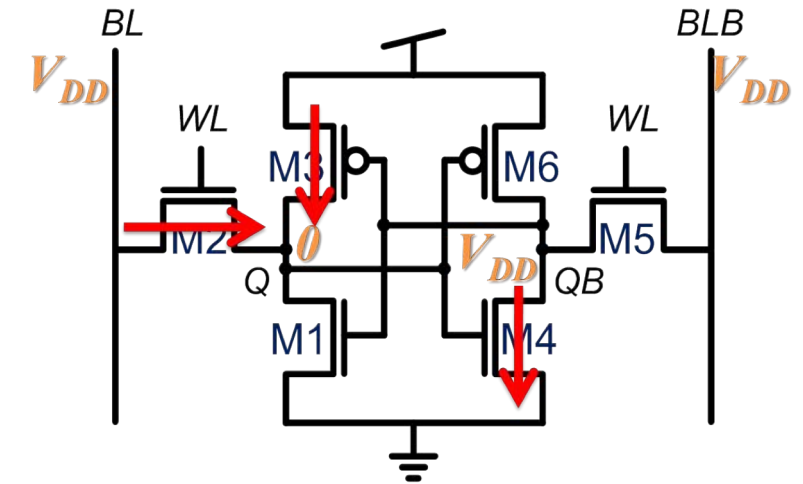
ULP energy-autonomous and
wearable devices



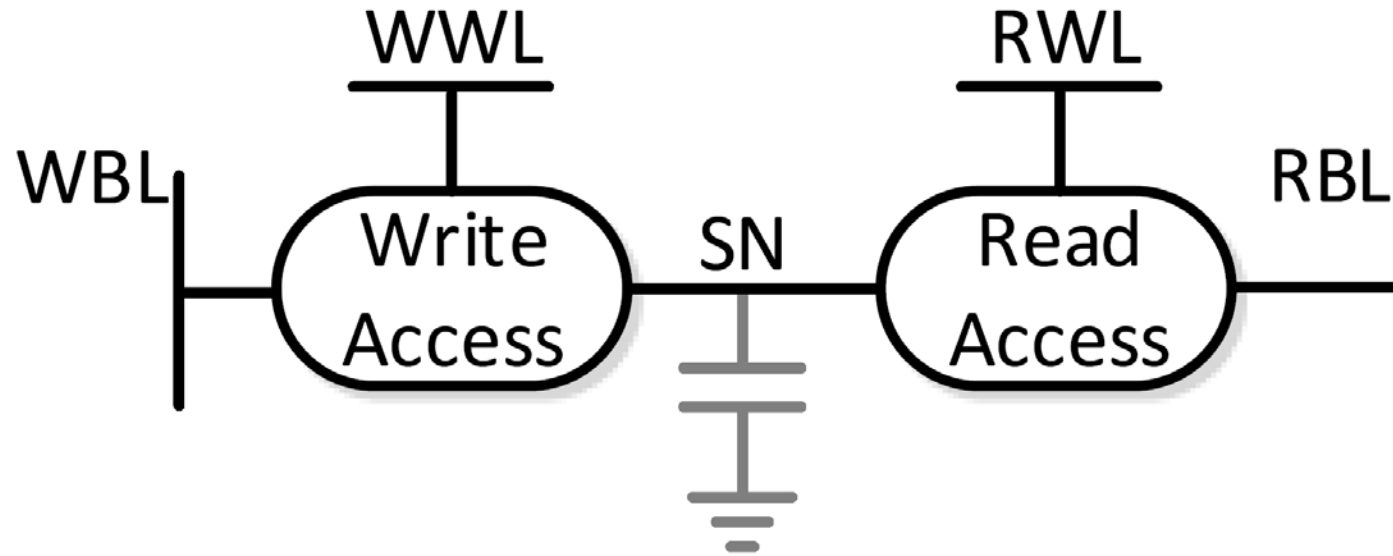
Operation for up to 10+ years on single battery charge

On-Chip SRAM Limitations

- Almost all integrated circuits rely on the standard 6T-SRAM bitcell for on-chip memory
- However, it incurs several limitations:
 - Six transistors per bit (6T)
 - Considerable static power due to leakage
 - Ratioed operation limits voltage scaling
 - Two port operation requires 8T



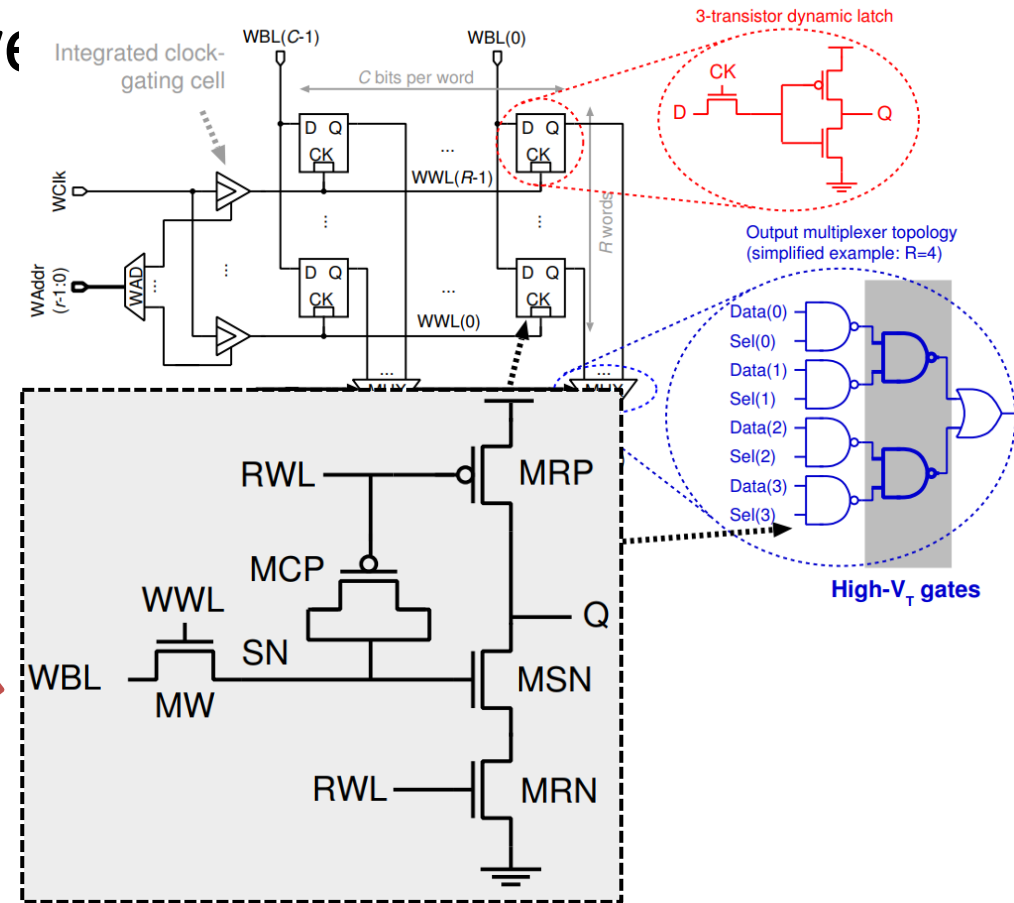
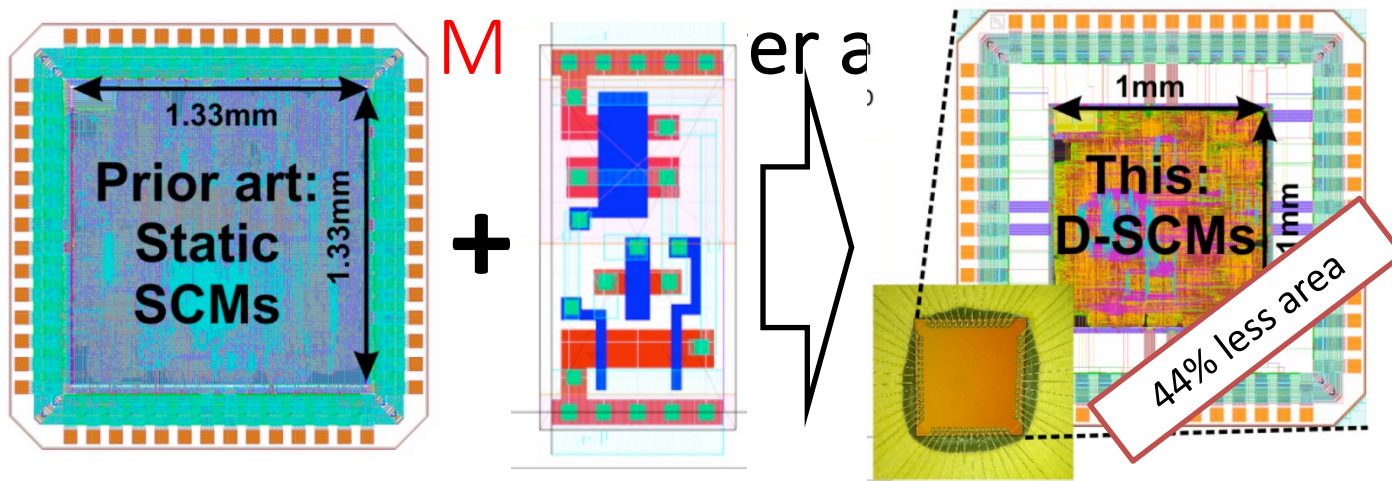
Basic Concept of Gain Cell eDRAM (GC-eDRAM)



Data is stored as charge with read- and write-access networks with 1-2 transistors each

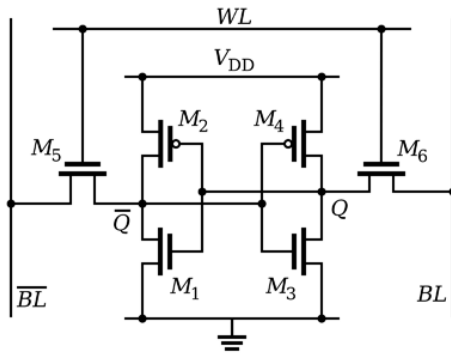
Refresh-free GC-eDRAM for DSP Applications

- DSP applications require many small memories for short-term storage
- Standard-cell memories offer $\sim 40\%$ power macros and enable voltage-scaling
 - However, with considerable area overhead
- Replacing latches with dynamic

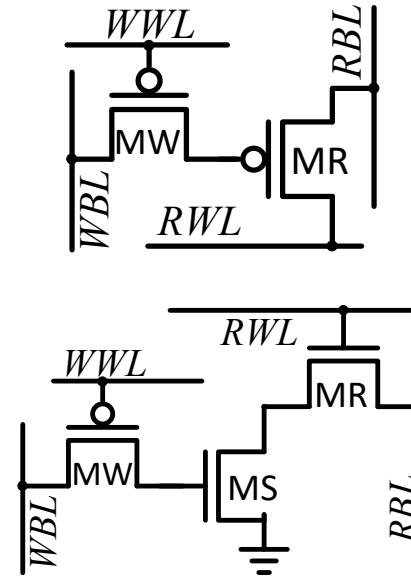


Gain Cell Embedded DRAM (eDRAM)

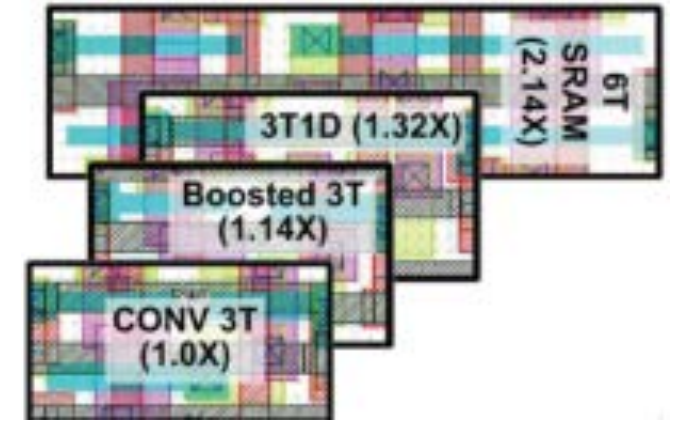
- Most compact realization: 2-3 transistors (2T and 3T gain cell)
 - Bit-cell area offers almost a 2x advantage over SRAM



6T-SRAM macros with an area of $130F^2$ per bit

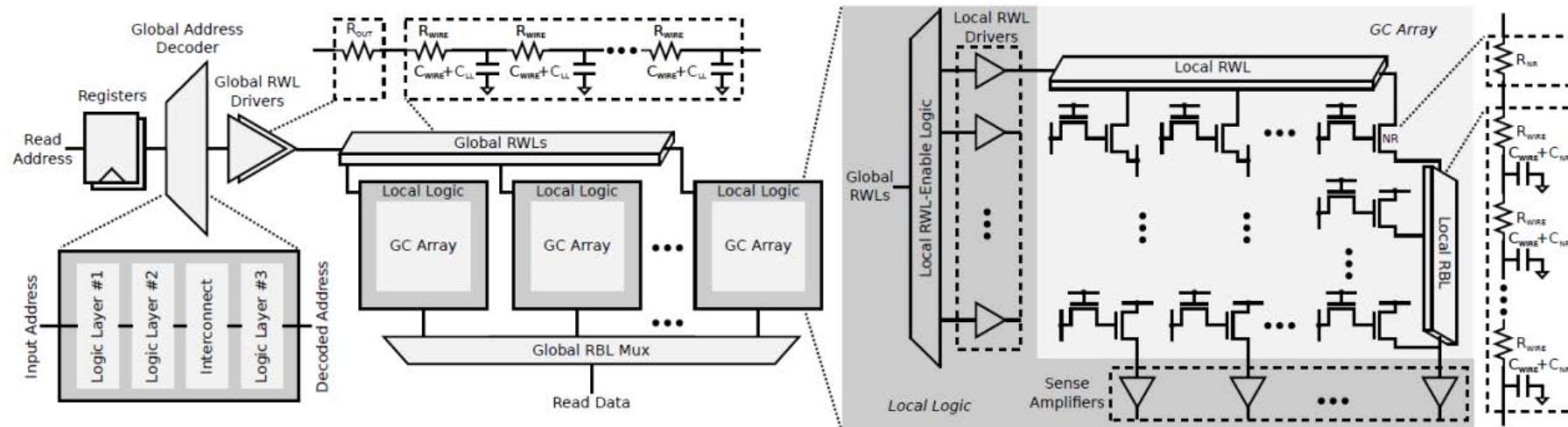


2T and 3T Gain Cell with $\sim 70F^2$ per bit



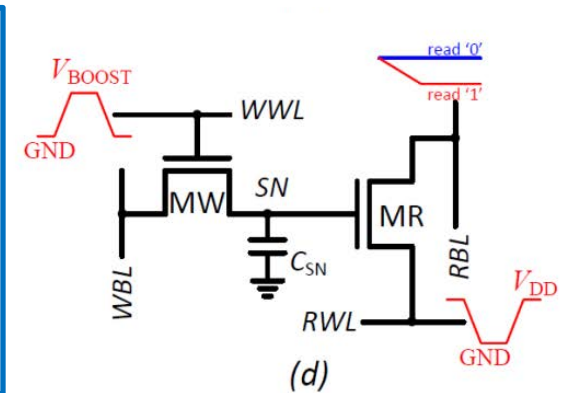
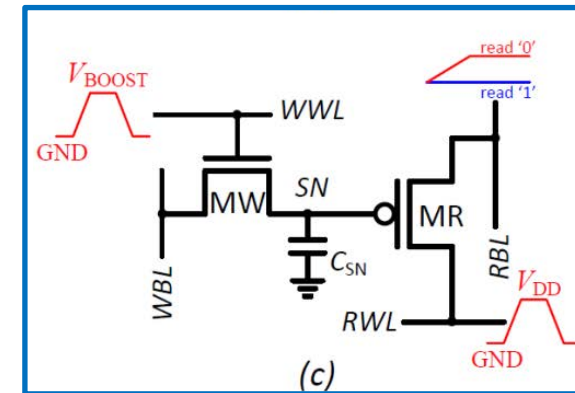
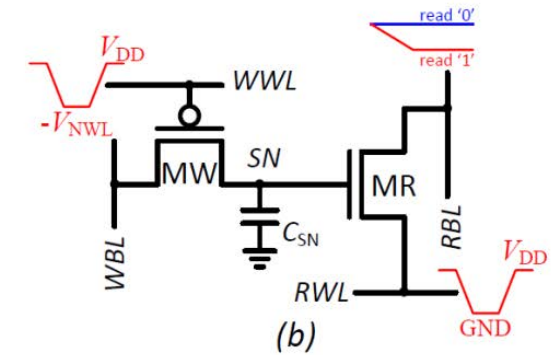
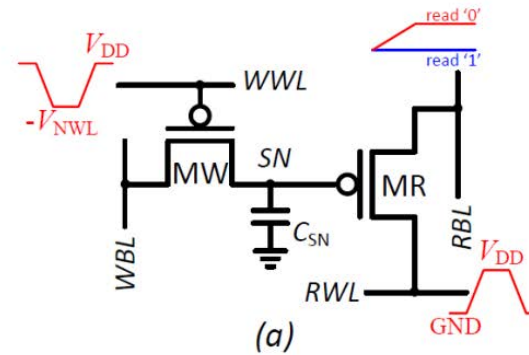
Gain Cell Embedded DRAM (eDRAM)

- Gain cells can be arranged in compact arrays with simple read- and write-access circuitry
 - Hierarchical arrangement of sub-arrays for large memories
 - Simple area-efficient peripherals
- Gain cell arrays are not more complex than SRAM arrays



2T Gain Cell eDRAM: Basic Operating Principle

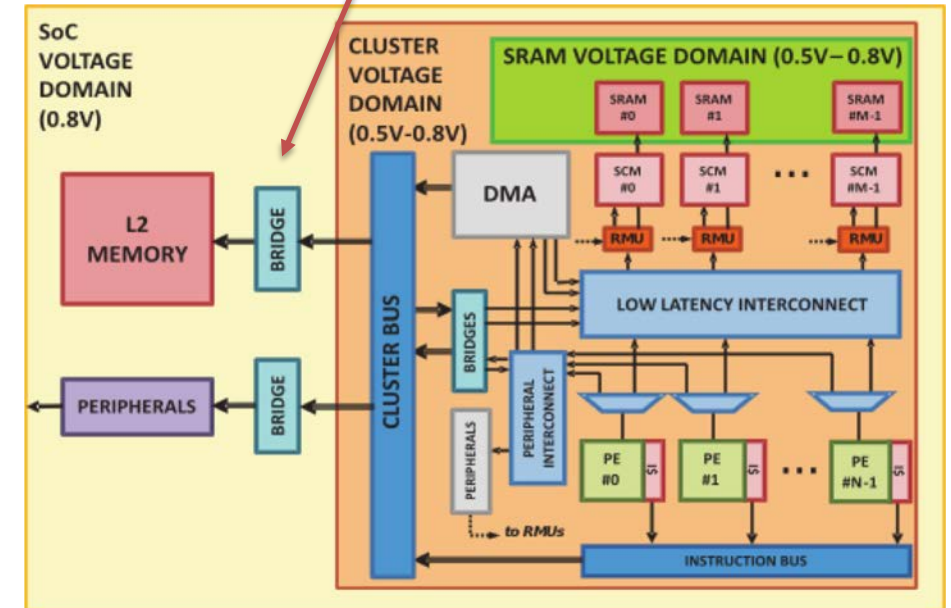
- **Write port (WWL & WBL)**, storage cap, and **read port (RWL & RBL)**
 - Different combinations of PMOS and NMOS transistors
 - Use of different threshold options
- **Write operation:**
 - Boosted WWL, above V_{DD} for NMOS, below V_{SS} for PMOS
- **Read:**
 - PMOS MR: Pre-discharge RBL, raise RWL
 - NMOS MR: Precharge RBL Lower RWL



Gain Cell eDRAM Requires Periodic Refresh

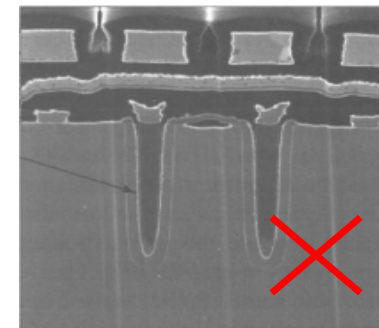
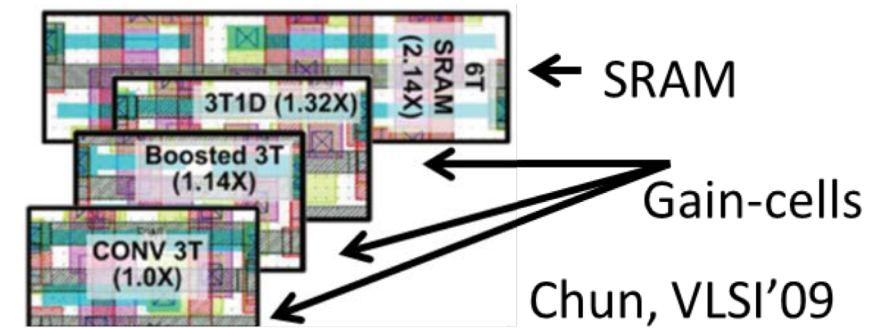
- Typical application of eDRAM: IoT SoCs:
 - Multi-level memory hierarchy with a high-capacity L2 memory
 - Connected to processor through a shared bus (stalls are not unusual)
 - Processor supported by at least one level of cache
 - L2 memory supported by a dedicated memory controller
- **L2 memory access in short bursts with long idle periods ($\gg 75\%$) that allow to hide refresh with almost no overhead**

Memory interface idle for at least 75% of the time

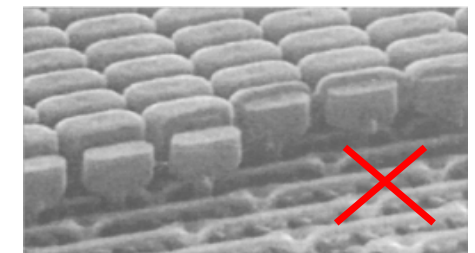


Gain-Cell Embedded DRAM Advantages

- Gain Cells have several advantages over conventional 6T SRAM and over 1T-1C eDRAM
 - **Smaller** cell size than SRAM, **less bitcell leakage**
 - Compared to 1T-1C eDRAM:
 - **Logic-compatible**, i.e., no special processing steps, and no extra cost
 - **Non-destructive read operation**
 - Naturally **support two-port operation**
 - Can be **optimized for read-ability AND write-ability**
 - Operational under near/sub-threshold voltages
 - Often **lower retention power** (leakage+refresh) than SRAM static power
 - **In many systems refresh can be hidden with almost no overhead**



Trench cap



Stacked caps

Kang, McGraw-Hill

GC eDRAM is an Attractive Alternative for Many Applications

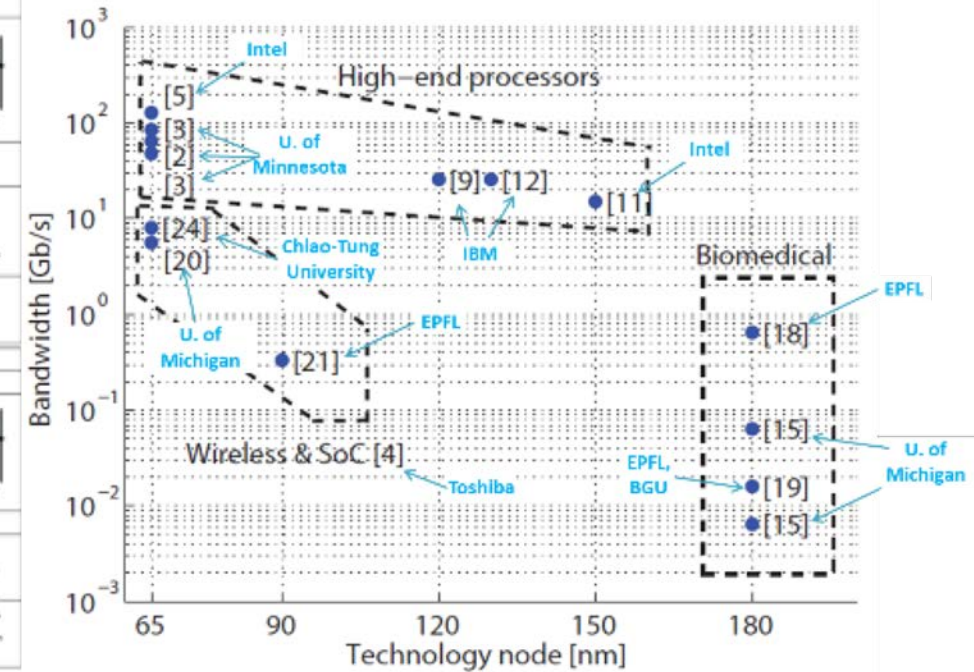
- GC-eDRAM is a class of memory with many different flavors
- Different bit-cells offer a wide range of design trade-offs between area, retention time, access delay, and power consumption

Category	High Performance Processor Caches					
Publication	[9,12,24]	[11]	[13]	[5,22]	[2,14]	[3]
Bitcell						
Tech. Node	0.12 μm, 0.13 μm, 65 nm PTM	0.15 μm	90 nm	65 nm	65 nm	65 nm
Techniques	Gated Diode, Footer Power Gating, Foot Driver	Multi Level Bitcell	DDT Classification	Boosted 3T	Half Swing WBL, Stepped WWL	Half Swing WBL, Stepped WWL
Main Design Metric	400 MHz, 70 μs retention, 100 kb	100 μs retention, 1 Mb	110 μs retention, 40 kb	10 μs retention, 2 Mb	up to 1.25 ms ret., 64 kb	667 MHz, 110 μs ret., 192 kb
Category	General SoC		Wireless	Low Power Biomedical Systems		
Publication	[10]	[8,21]	[20]	[15]	[18]	[19]
Bitcell						
Tech. Node	90 nm	90 nm	65 nm	0.18 μm	0.18 μm	0.18 μm
Techniques	Forward Bias Back	Multi Level Bitcell	Refresh Free, Sequential Decoding	I/O Write Transistor, Low Area Sense Buffer	Low Area Sense	Hybrid Cell with I/O MW, Sense Buffer
Main Design Metric	SoC & Wireless		32 × 1 kb arrays, 700 MHz, 170 ns retention	V _{DD} =0.75 V, up to 3 ms ret., 0.1–1 MHz	LV/LP	

Caches for high-end processors

SoC & Wireless

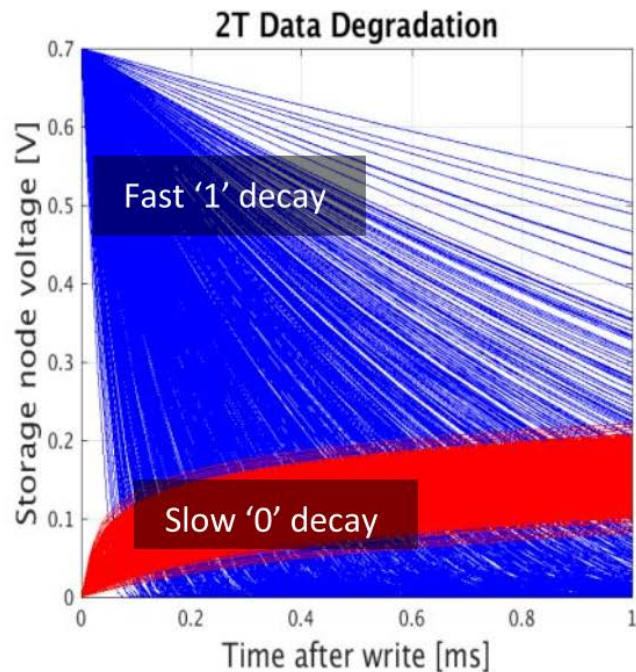
LV/LP



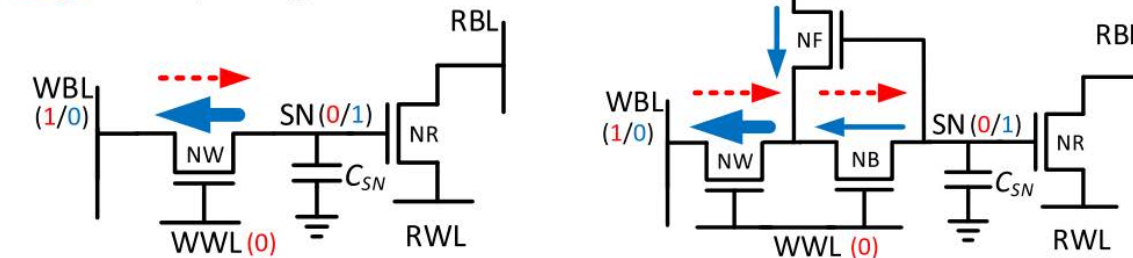
Source: Teman, et al., 2012

GC-eDRAM is also feasible for nm-CMOS Nodes

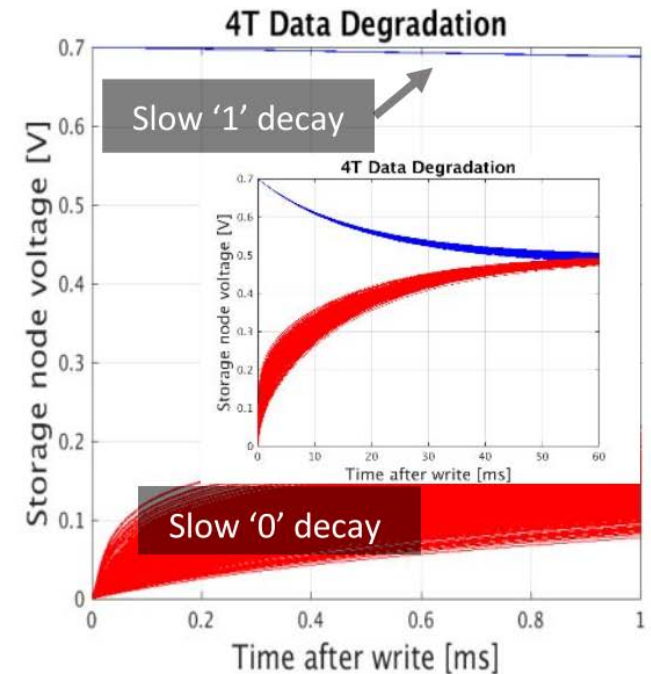
- Advanced process nodes suffer from high leakage currents
- eDRAM has been considered infeasible below 65nm
- **4T bit-cell topology** provides feedback for weak data level and enables eDRAM with milliseconds retention time in 28nm CMOS



→ Pull down leakage
→ Pull up leakage

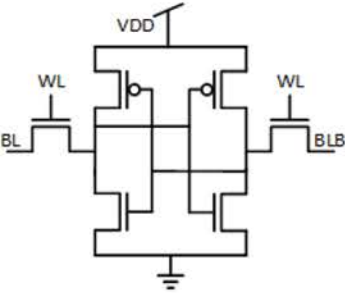
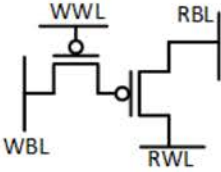
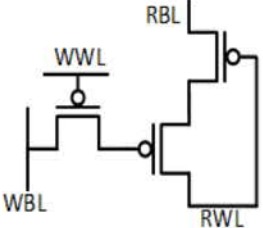
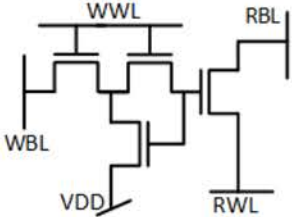


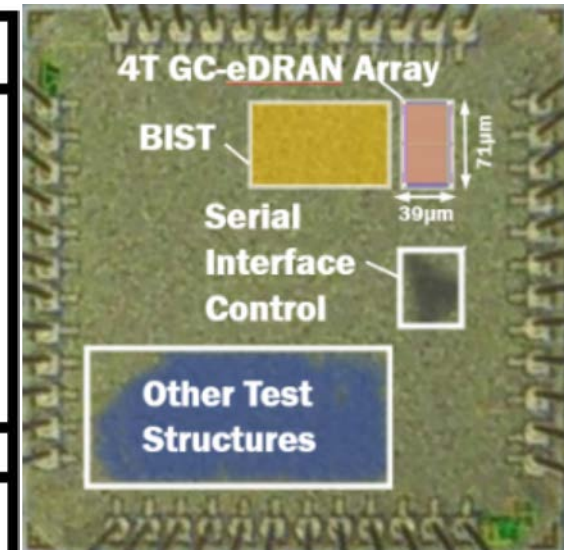
30-40X retention time w.r.t. 2T



High Density Low Power GC-eDRAM in 28nm FD-SOI

- Clear area reduction compared to SRAM with sufficient retention

	6T SRAM	2T Gain-Cell	3T Gain-Cell	Our 4T Gain-Cell
Cell Structure				
Technology Node	28nm FD-SOI	28nm FD-SOI	28nm FD-SOI	28nm FD-SOI
Cell Size (μm^2) (Non-pushed logic design rules)	$0.325\mu\text{m}^2$ [1X]	$0.152\mu\text{m}^2$ [0.47X]	$0.186\mu\text{m}^2$ [0.57X]	$0.23\mu\text{m}^2$ [0.71X]
8Kbit Macro Size (μm^2)	$3321\mu\text{m}^2$ [1X] Pushed SRAM design rules	N/A	N/A	$2769\mu\text{m}^2$ [0.83X] Non-pushed logic design rules
Supply Voltage	700mV	700mV	700mV	700mV
Data Retention Time	Static	$32\mu\text{s}$ @ 27C * $3.1\mu\text{s}$ @ 85C *	$51\mu\text{s}$ @ 27C * $4.14\mu\text{s}$ @ 85C *	$1691.4\mu\text{s}$ @ 27C ** $154.95\mu\text{s}$ @ 85C **
Array Retention Power*	$74.3\text{nW}/8\text{Kb}$ @ 27C $1.36\mu\text{W}/8\text{Kb}$ @ 85C	$2.1\mu\text{W}/8\text{Kb}$ @ 27C $22\mu\text{W}/8\text{Kb}$ @ 85C	$1.4\mu\text{W}/8\text{Kb}$ @ 27C $16.8\mu\text{W}/8\text{Kb}$ @ 85C	$57.37\text{nW}/8\text{Kb}$ @ 27C $909.34\text{nW}/8\text{Kb}$ @ 85C

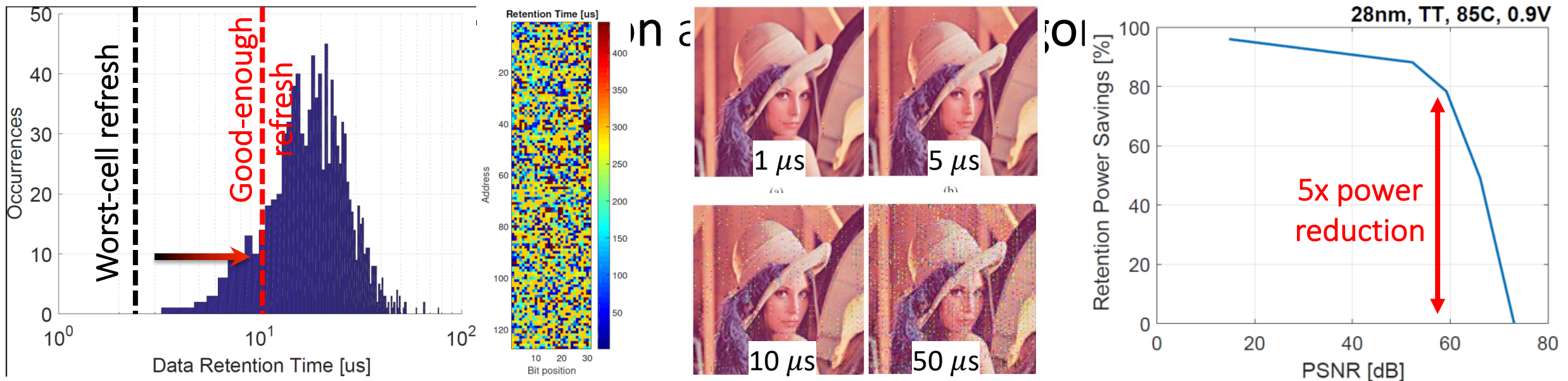


*Simulated **Measured

Source: R. Giterman, A. Fish, A. Burg and A. Teman, IEEE Transactions on Circuits and Systems I (TCAS-I), August 2017

Approximate Computing with Unreliable (eDRAM) Memory

- Manufacturing inaccuracies and different operating conditions lead to variations in the circuit behavior within each chip and between chips
 - Conventional solution: refresh with guardbands for 100% reliable operation
- **Computing with unreliable memories: relax refresh and accept errors**



Conclusions

- Memory is the limiting factor in area and power for almost all integrated circuits
- 6T SRAM is well established, but consumes large area and power and limits voltage scaling
- **GC-eDRAM is a real alternative for SRAM**
 - Area and energy efficient
 - Refresh can be hidden in many applications
 - Is feasible in advanced technology nodes (28nm and below)
 - GC eDRAM provides further potential when combined with new fault tolerant computing paradigms such as approximate computing or AI

